Amendments to the Specification:

Kindly replace paragraph [0022] starting on page 6 and ending on page 7, with the following replacement paragraph:

Referring to the drawings in general and to Figure 1 in particular, it will be understood that the illustrations are for the purpose of describing a preferred embodiment of the invention and are not intended to limit the invention thereto. An apparatus 100 for depositing a uniform coating on a macroscopically planar - or flat - surface using a plurality of expanding thermal plasma sources is schematically shown in Figure 1a. The apparatus 100 shown in Figure 1a has been described in "Apparatus and Method for Large Area Chemical Vapor Deposition Using Expanding Thermal Plasma Generators," U.S. Patent Application 09/681,820, by Barry Lee-Mean Yang et al., now U.S. Pat. No. 6,397,776, and in "~~Large Area Plasma Coating Using Multiple Expanding Thermal Plasma Sources in Combination with a Common Injection Source~~ Apparatus and method for depositing large area coatings on planar surfaces," U.S. Patent Application 09/683149, by Marc Schaepkens, now U.S. Pat. No. 6948448, both of which are commonly assigned and incorporated herein by reference in their entirety. A coating 132 is deposited on the surface 134 of a planar substrate 130 as the planar substrate 130 is scanned in front of an array 110 of a plurality of expanding thermal plasma (hereinafter also referred to as "ETP") sources 112. Alternatively, substrate 130 may be statically mounted in front of array 110. Each of the plurality of ETP sources 112 is supplied with at least one reactant gas injector 140 that injects a reactant gas into each of the plurality of plasmas generated by each of the plurality of ETP sources 112. The reactant gas then reacts with the generated ETP to form coating 132. The at least one reactant gas is supplied at the same flow rate to each of the plurality of ETP sources 112 to produce a coating having uniform properties, as represented by the uniform distribution or linear density of reactant gas injectors in Figure 1a.